IN THE CLAIMS AMEND

1. An optical arrangement, comprising a microlithographic projection printing installation having a rotationally non-symmetrical illumination, comprising a light source which emits radiation, and an optical element which is heated by being acted upon by the radiation, and a supply apparatus for gas tempering the optical element,

wherein,

the supply apparatus (11, 19 to 23) comprises at least one supply line (21) and at least gas directing device (11), which is aligned relative to the optical element (5) and controllable in such a way that the gas is directed by the gas directing device (11) as a free flow towards the optical element (5) and the volumetric flow of the exiting gas has a magnitude and spatial distribution (17), which are adapted to the intensity distribution (6) of the radiation (1).

12. An optical arrangement as claimed in one of the preceding claims, wherein the gas directing device (11) is part of a sweeping device for the optical element (5).

IN THE CLAIMS ADD

14. An optical arrangement as claimed in one of the preceding claims, wherein the gas directing device (11) is part of a sweeping device for the optical arrangement (4, 5).